

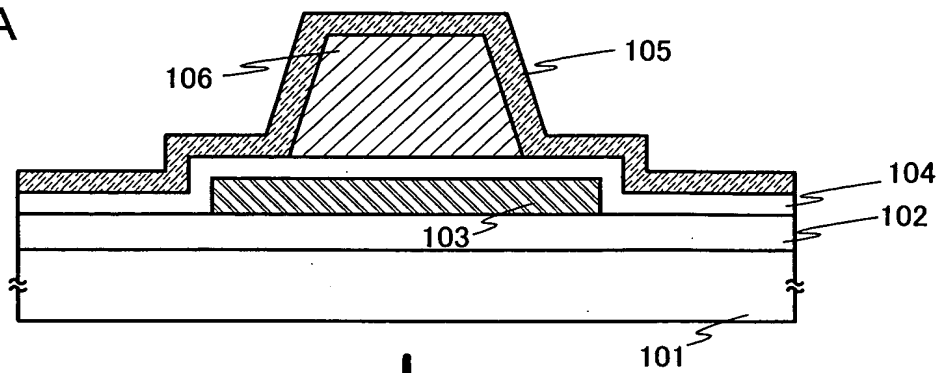
Table 1

base film sample	SiN			SiO ₂		
	SiN(a)	SiN(b)	SiN(c)	SiO ₂ (a)	SiO ₂ (b)	SiO ₂ (c)
hydrofluoric acid treatment (120sec)	○			○		
hydro washing (60sec)		○			○	
hydrofluoric acid treatment (120sec)		○			○	
water washing		○			○	
heat-treatment (150°C, 3min)		○			○	
applying a positive photosensitive acrylic resin		○			○	
washing periphery of sample		○			○	
exposure		○			○	
development		○			○	
water contact angle (degree)(after deposition)	50			44		
wettability of the positive photosensitive acrylic resin (after applying)	○	○	○	○	○	○
adhesiveness of patterns (after development)	○	○	○	x	x	○

Table 2

base film sample	SiON			SiO ₂		
	SiON(a)	SiON(b)	SiON(c)	SiO ₂ (a)	SiO ₂ (b)	SiO ₂ (c)
hydrofluoric acid treatment (120sec)	○			○		
hydro washing (60sec)		○			○	
hydrofluoric acid treatment (120sec)		○			○	
water washing		○			○	
heat-treatment (150°C, 3min)		○			○	
applying a positive photosensitive acrylic resin		○			○	
washing periphery of sample		○			○	
exposure		○			○	
development		○			○	
water contact angle (degree)(after deposition)	24			15		
wettability of the positive photosensitive acrylic resin (after applying)	○	○	○	○	○	○
adhesiveness of patterns (after development)	x	x	x	x	x	x

Fig. 1A



hydrogenation by heating



Fig. 1B

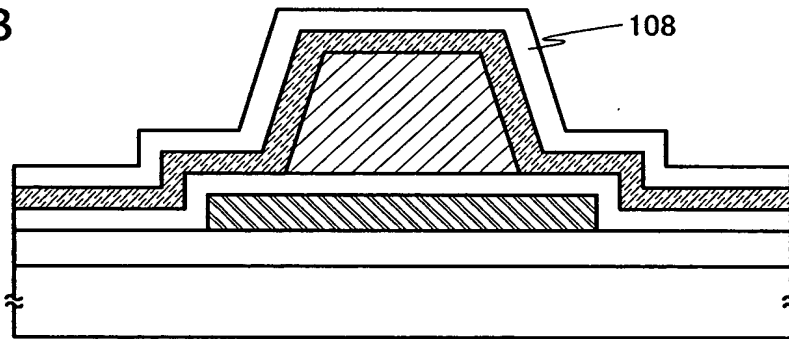


Fig. 1C

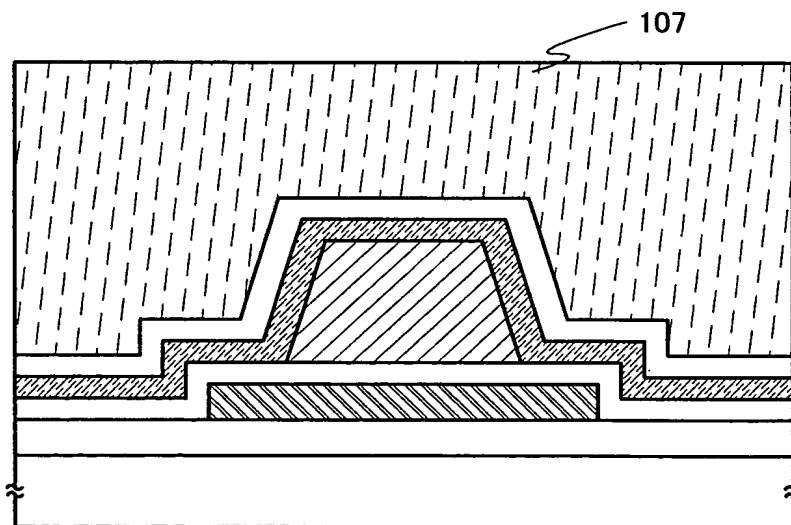
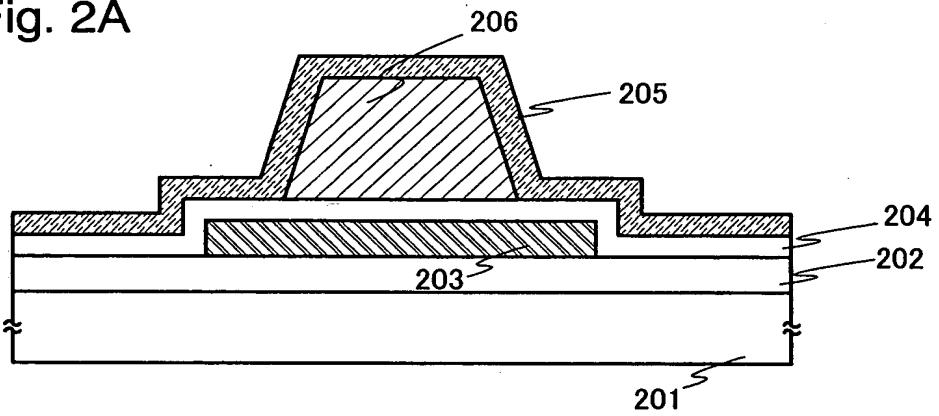


Fig. 2A



hydrogenation by heating

Fig. 2B

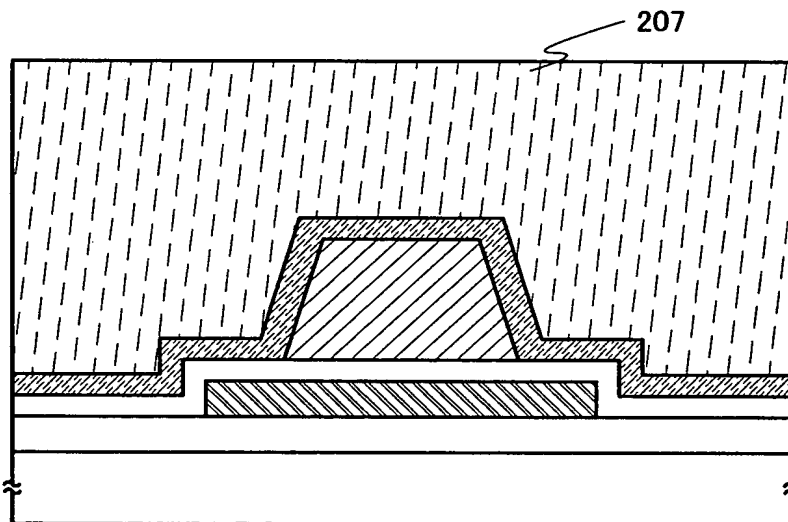


Fig. 3A

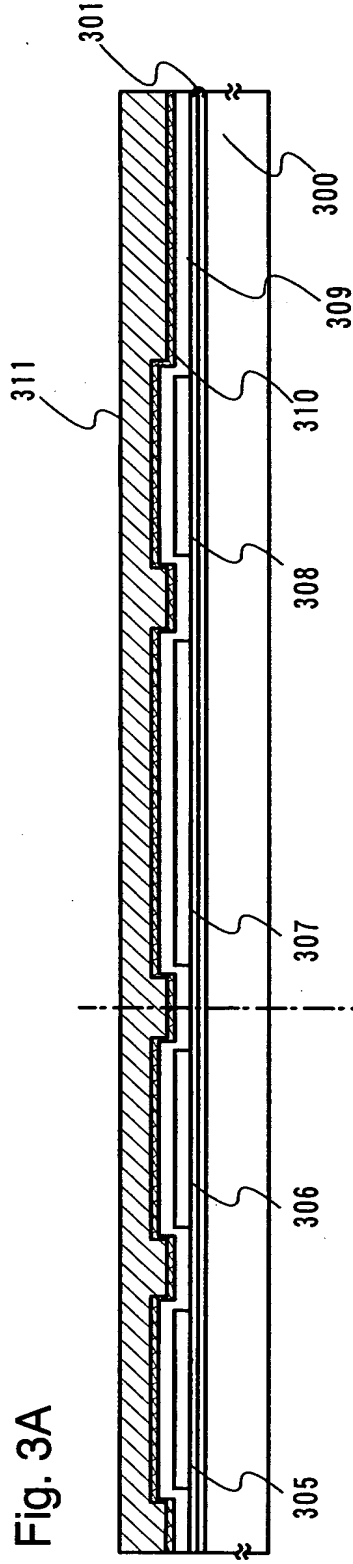


Fig. 3B

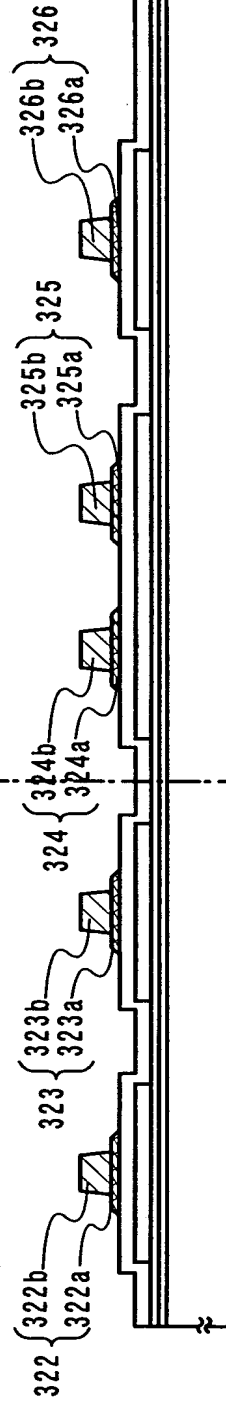
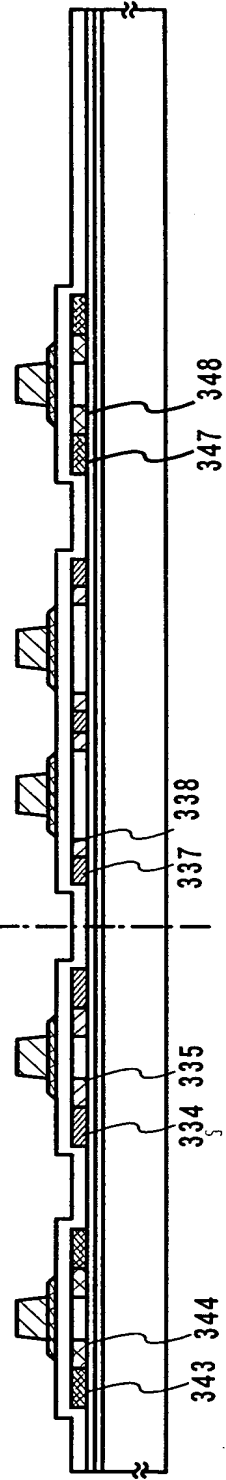
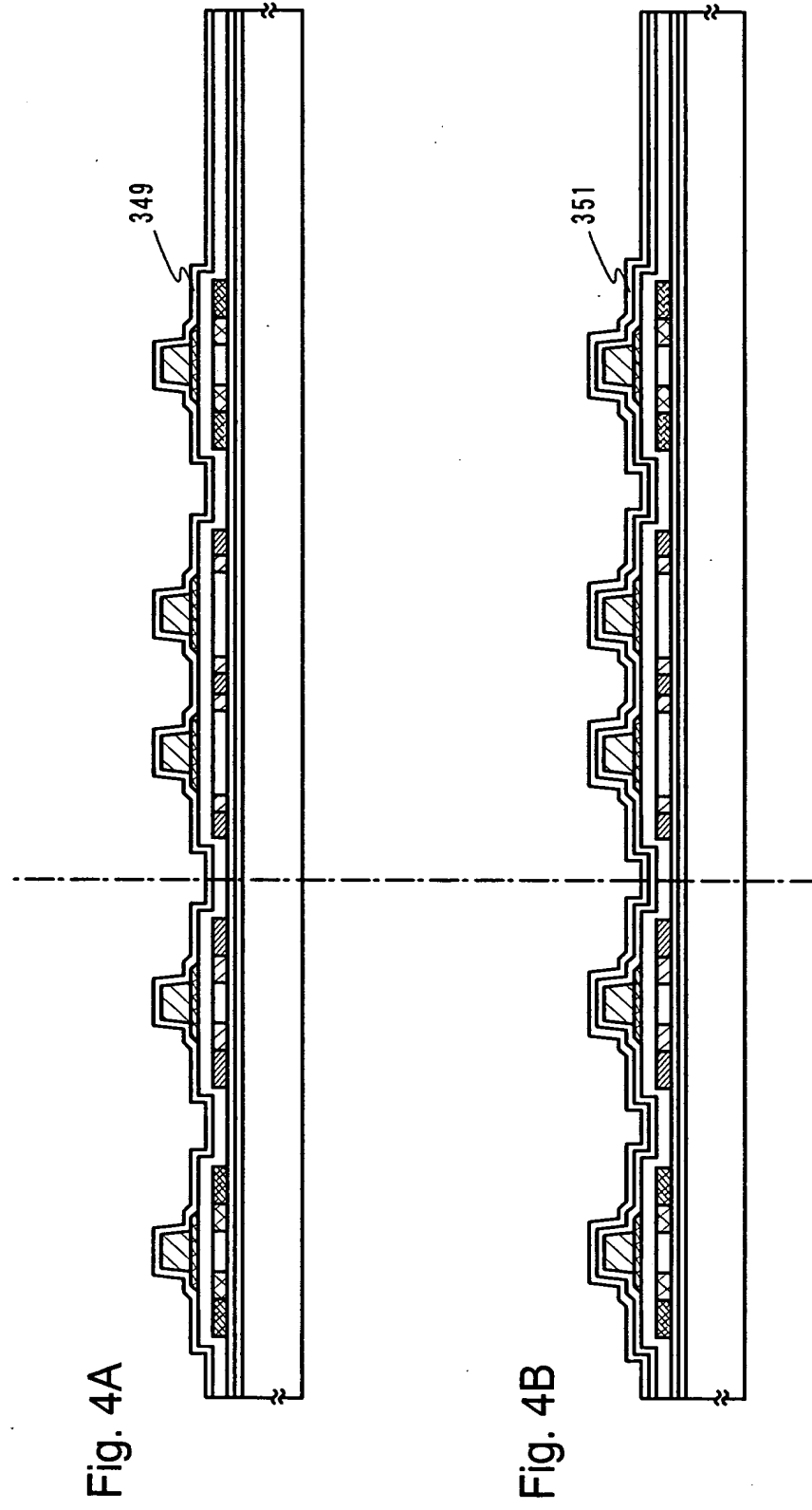


Fig. 3C





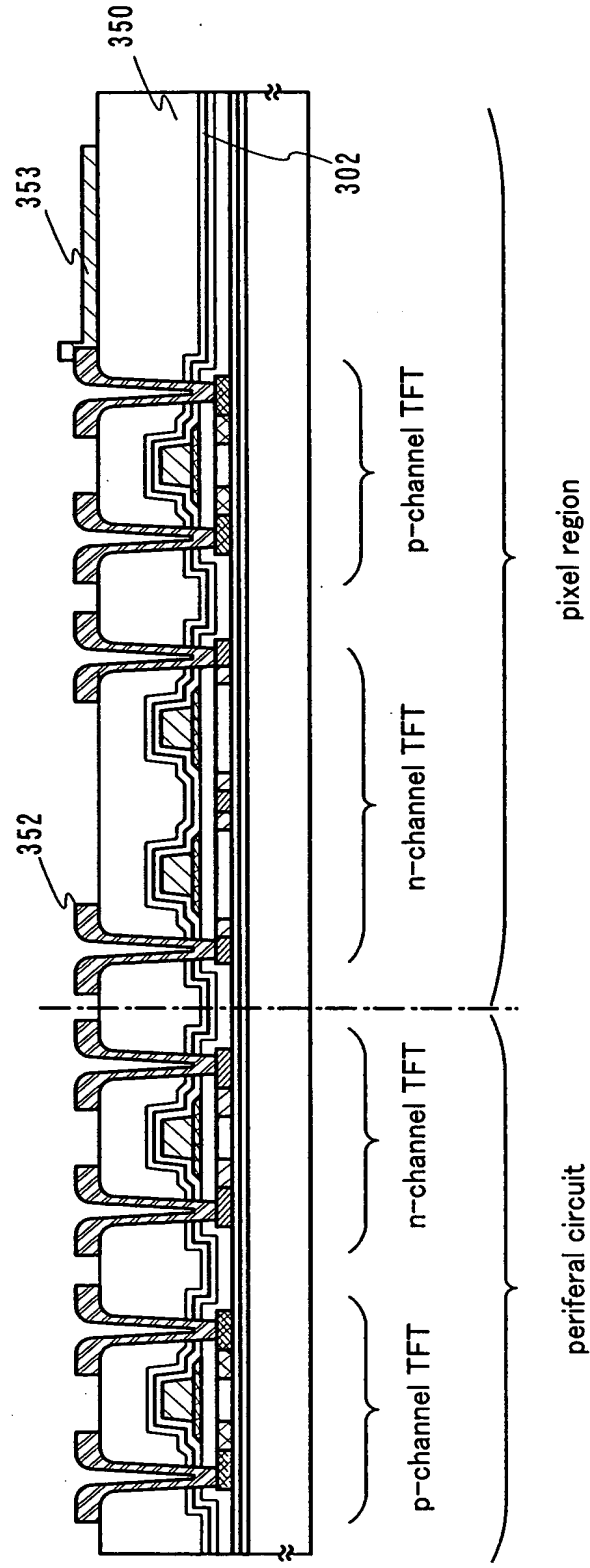


Fig. 5

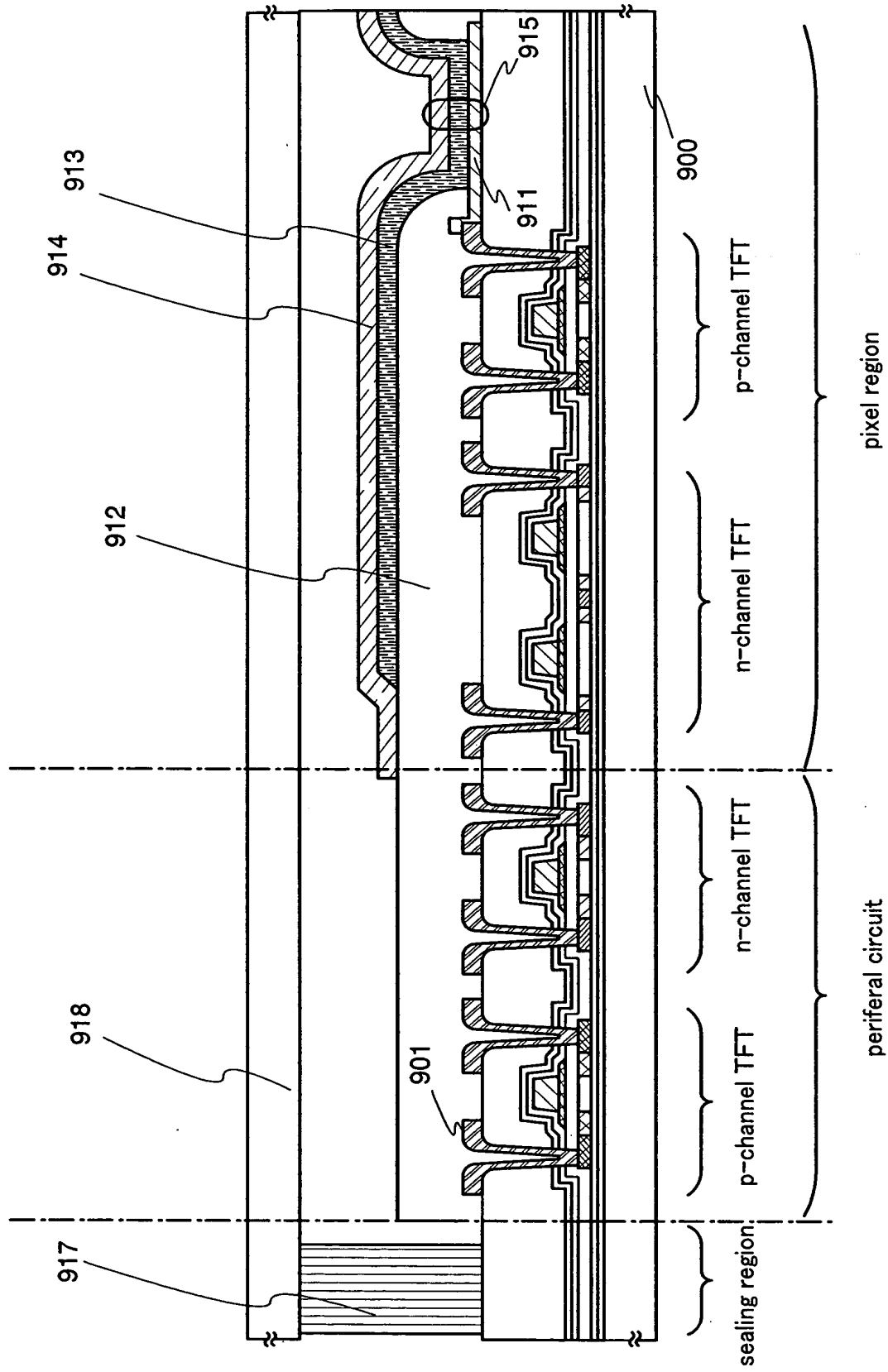


Fig. 6

Fig. 7A

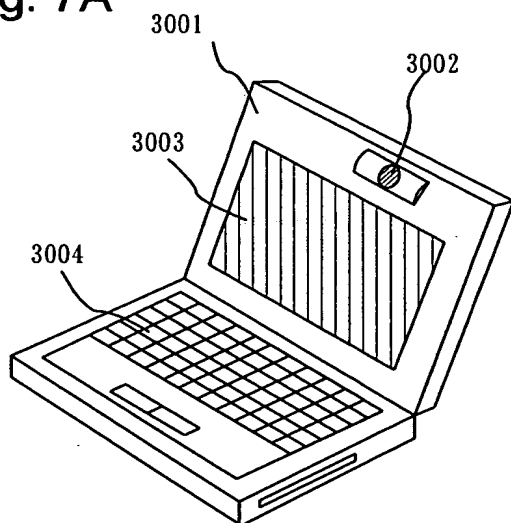


Fig. 7B

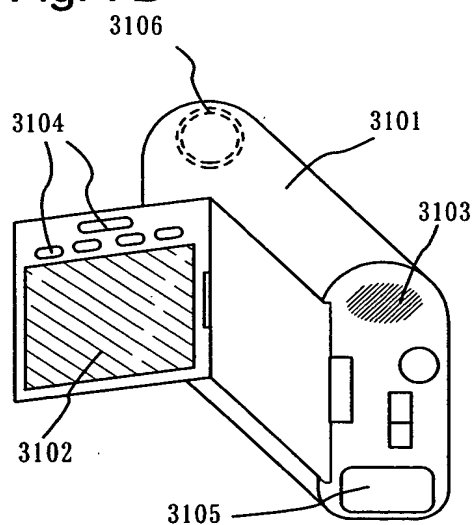


Fig. 7C

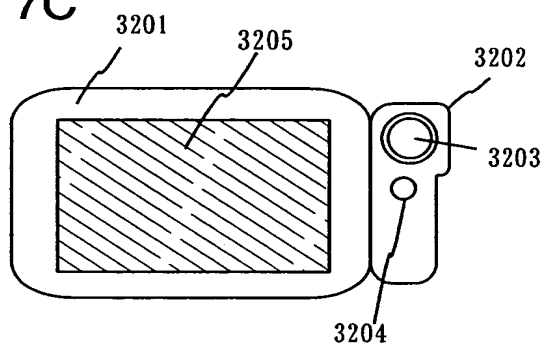


Fig. 7D

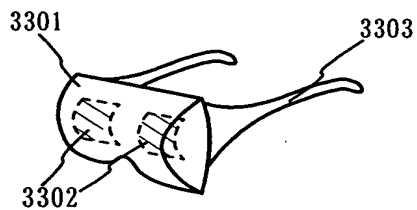


Fig. 7E

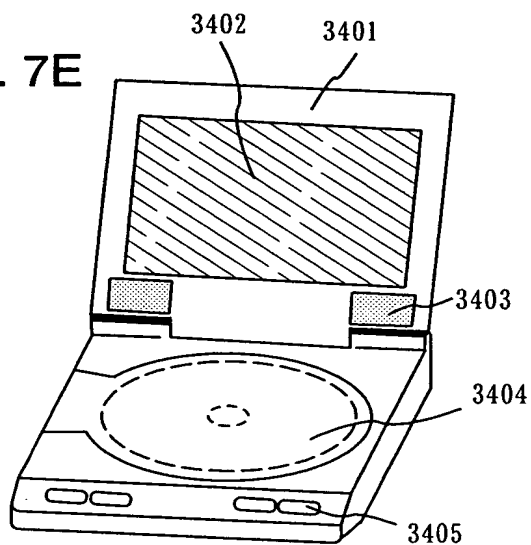


Fig. 7F

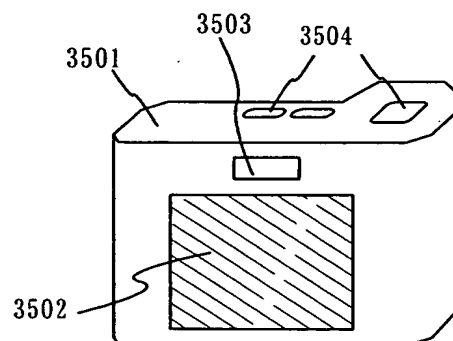


Fig. 8A

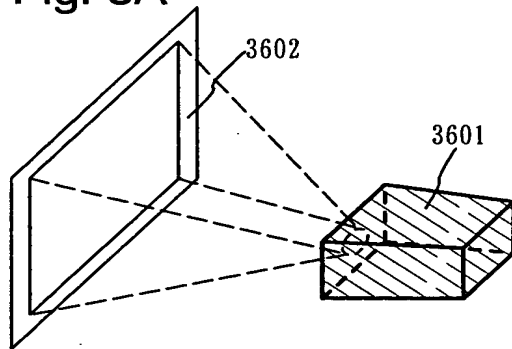


Fig. 8B

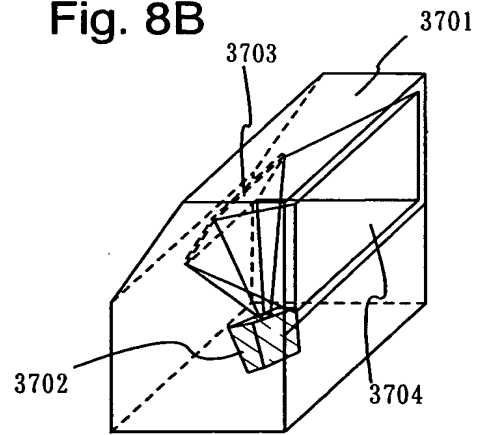


Fig. 8C

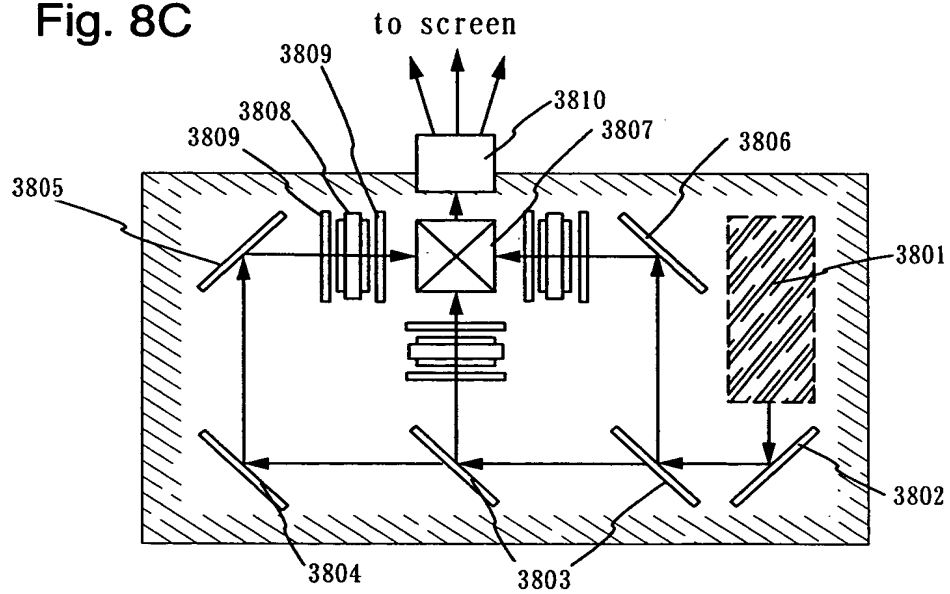


Fig. 8D

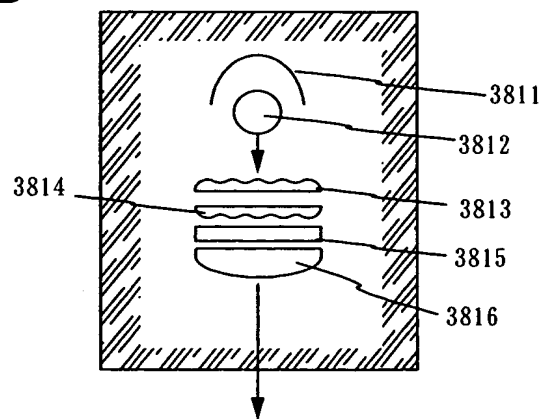


Fig. 9A

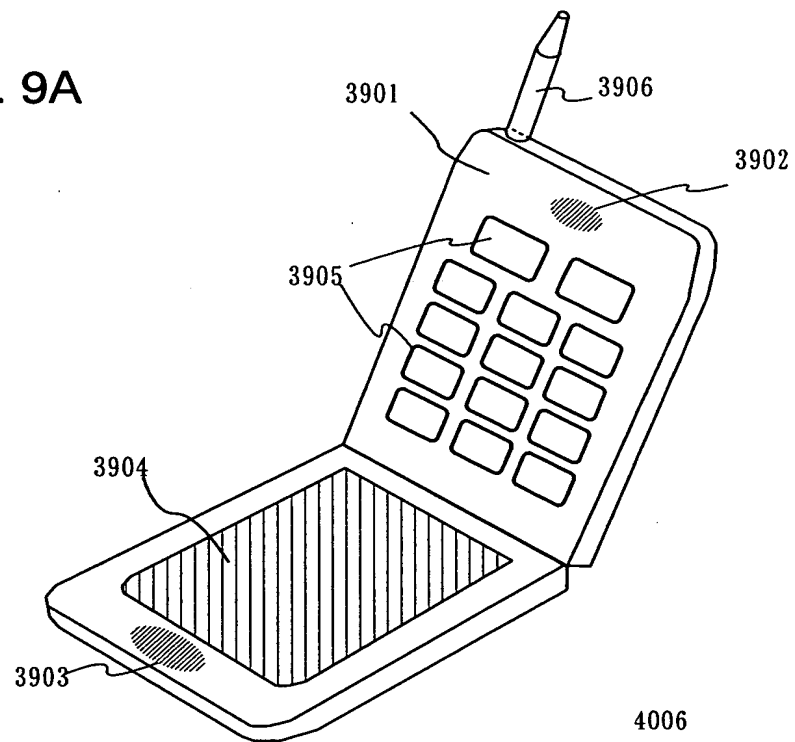


Fig. 9B

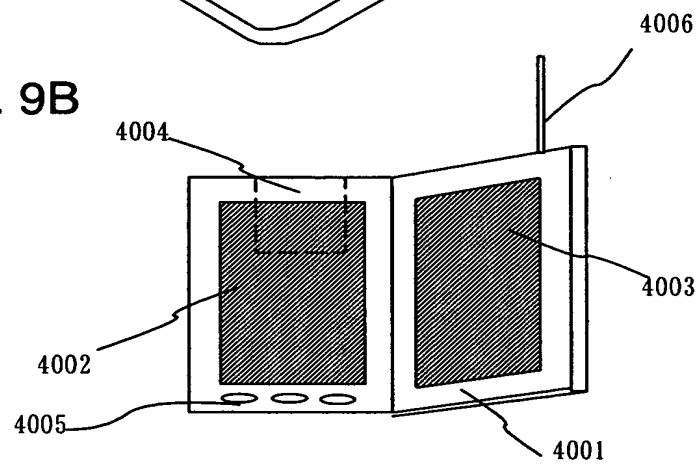
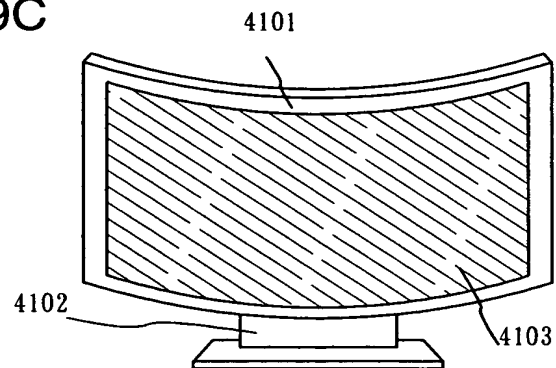


Fig. 9C



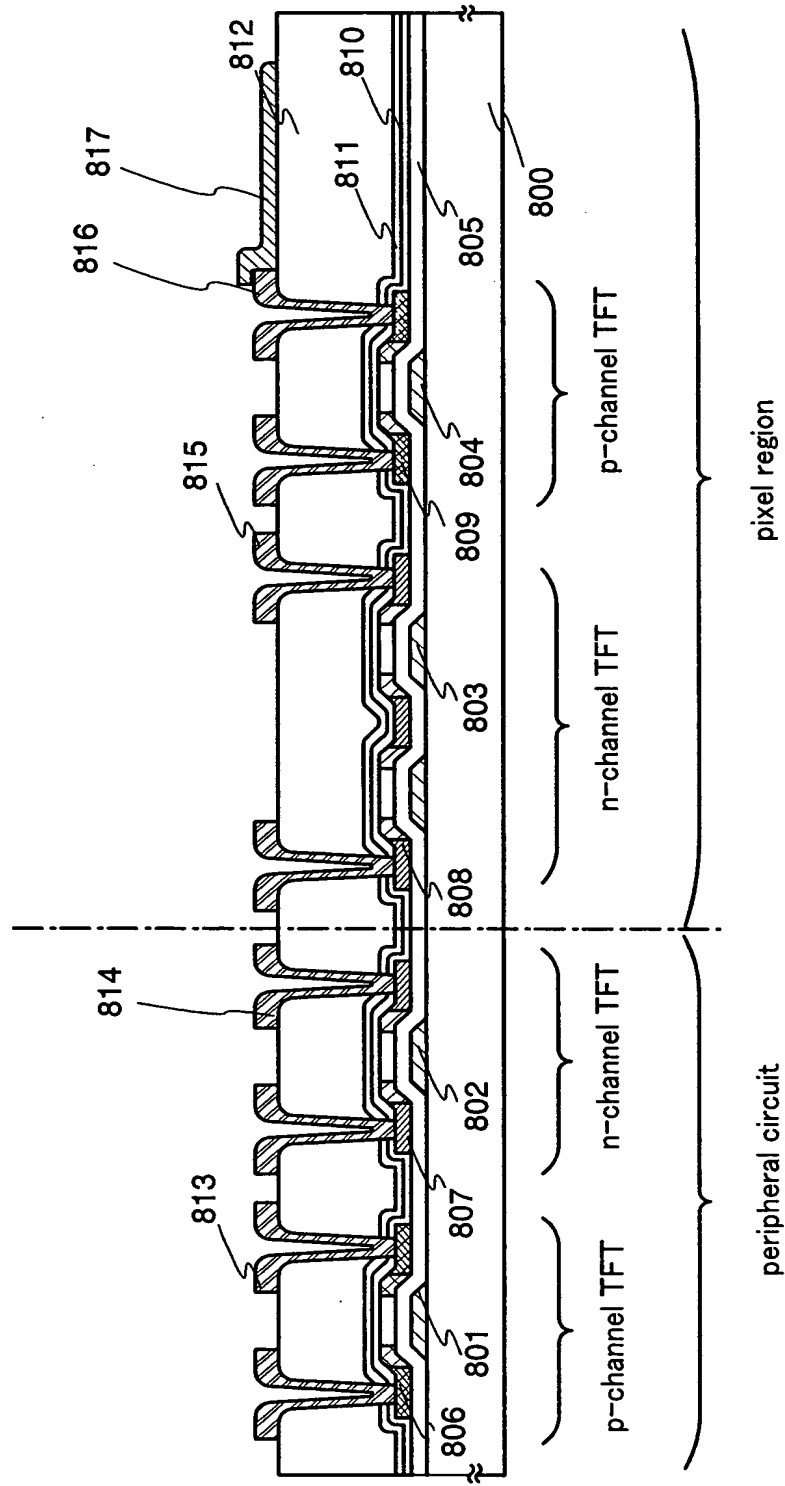


Fig. 10